

Amendments in the claims:

Please amend claims 1-4, 8-11 and 13 and add new claims 15-17 as indicated below.

Claims 1-4 and 8-17 are now pending.

This listing of claims will replace all prior versions and listings of claims in the application.

Claim 1 (Currently Amended): An organic film vapor deposition method comprising:

a first step of supporting a multi-sided substrate, having a scintillator formed on a first side of the substrate, formed with a scintillator on at least three protrusions of a target-support element, the scintillator covering a substantial portion of the first side of the substrate, with at least one portion of the first side of the substrate being uncovered by the scintillator disposed on a rotatable vapor deposition table so as to maintain a distance from said vapor deposition table; and

~~a second step of introducing said rotatable vapor deposition table having said substrate supported by said target support element into a vapor deposition chamber of a CVD apparatus;~~
and

a ~~third~~ second step of depositing an organic film by a CVD method onto substantially all exposed surfaces of said substrate, ~~provided with~~ and said scintillator, ~~introduced into said vapor deposition chamber in a state that said substrate is supported so as to maintain a distance from said rotatable vapor deposition table~~ including a second side of the substrate opposite the first side of the substrate as well as the portion of the first side of the substrate uncovered by the scintillator.

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Claim 2 (Currently Amended): An organic film vapor deposition method according to claim 1, wherein said target-support element ~~is constituted by~~ comprises at least three target-support needles.

Claim 3 (Currently Amended): An organic film vapor deposition method according to claim 1, wherein said target-support element ~~is constituted by~~ comprises a strand member.

Claim 4 (Currently Amended): An organic film vapor deposition method according to claim 1, wherein said organic film ~~[[is]]~~ comprises a polyparaxylylene film.

Claims 5-7 (Canceled).

Claim 8 (Currently Amended): An organic film vapor deposition method according to claim 1, wherein ~~the rotatable vapor deposition table comprises a turntable,~~ during at least the second step, the target support element is disposed on a rotatable vapor deposit table so as to maintain a distance between the substrate with the scintillator formed thereon and the vapor deposition table.

Claim 9 (Currently Amended): An organic film deposition method according to claim ~~[[1]]~~ 8, where the ~~[[third]]~~ second step of depositing the organic film is performed while the vapor deposition table is rotating.

Claim 10 (Currently Amended): An organic film vapor deposition method according to claim 8, further comprising a ~~fourth~~ third step of depositing a second organic film by a CVD method onto substantially all exposed surfaces of the organic film deposited in the ~~third~~ second step.

Claim 11 (Currently Amended): An organic film vapor deposition method according to claim 10, wherein the ~~fourth~~ third step comprises supporting the substrate, after having the organic film deposited in the ~~third~~ second step formed thereon, on at least three protrusions of a target-support element disposed on the rotatable vapor deposition table, with the support positions of the protrusions in the ~~fourth~~ third step being shifted with respect to the support positions of the protrusions in the ~~first~~ second step.

Claim 12 (Previously Added): An organic film vapor deposition method according to claim 11, wherein the shifted positions of the support elements are configured to prevent film peeling.

Claim 13 (Currently Amended): An organic film vapor deposition method according to claim 1, wherein the first step comprises supporting multiple substrates, each formed with a scintillator, on at least three protrusions of respective target-support elements disposed on a vapor deposition table so as to keep a distance from said vapor deposition table; and

~~the second step comprises introducing said vapor deposition table having said substrates supported by said respective target support elements into a vapor deposition chamber of a CVD apparatus; and~~

the ~~third~~ second step comprises depositing, while said table is rotating, an organic film by CVD method onto all surfaces of each substrate provided with a scintillator and ~~introduced into~~ said positioned in a vapor deposition chamber of a CVD apparatus in a state such that each substrate is supported so as to keep a distance from said vapor deposition table.

Claim 14 (Previously Added): A method of making a scintillator panel comprising the steps of:

forming a scintillator on a substrate; and

forming an organic film according to claim 1.

Claim 15 (New): An organic film vapor deposition method according to claim 1, wherein a step of introducing a rotatable vapor deposition table having said substrate supported by said target-support element thereon into a vapor deposition chamber of a CVD apparatus, is performed between the first and second steps.

Claim 16 (New): An organic film vapor deposition method according to claim 1, wherein said scintillator is formed of columnar crystals.

Claim 17 (New): An organic film vapor deposition method according to claim 1, wherein, upon completion of said second step, said organic film has at least three support holes located at positions where said substrate was supported by protrusions of said target support member, respectively.